

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Appl. No. : Natl. Phase of PCT/JP2003/011137
Applicant(s) : Mitsuru UEDA *et al.*
Filed : herewith
TC/A.U. :
Examiner :
Docket No. : 28955.1048
Customer No. : 27890
Title : PHOTORESIST BASE MATERIAL, METHOD FOR
PURIFICATION THEREOF, AND PHOTORESIST COMPOSITIONS

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

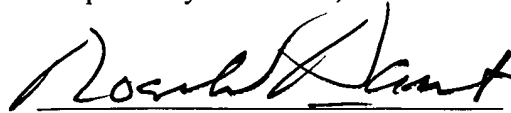
Sir:

Submitted herewith is a copy of the International Search Report ("ISR") in International Application PCT/JP2003/011137, the PCT counterpart of the above-referenced application. Attached is form PTO-1449 listing all the references cited in this ISR and the specification, as well as copies of the foreign patents.

The Commissioner is hereby authorized to charge any missing fees or credit any overpayment to Deposit Account 19-4293.

Respectfully submitted,

Date: 4/14/05


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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.